IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In the matter of the PATENT application of

Wilson Smart et al Inventor

SILICON NITRIDE WINDOW FOR MICROSAMPLING DEVICE Title

AND METHOD OF CONSTRUCTION

09/816,497 Ser.No. March 26, 2001 Filed

unassigned Patent Examiner 1743 Art Group Unit

Commissioner for Patents Washington D.C. 20231

October 19, 2001

PRELIMINARY AMENDMENT SUBMISSION OF SUBSTITUTE FORMAL DRAWING CLEAN COPY OF WRITTEN DESCRIPTION (under 37 CFR 1.121)

Sir;

This paper is submitted as a Preliminary Amendment to the above identified recently filed application. Please amend this application as follows:

IN THE DETAILED DESCRÍPTION:

2, line 12, AFTER "September"

CHANGE "I" to --1--.

DELETE "widely". 2, line 27, Page

2, line 31, AFTER "Further,"

CHANGE "it" to --the window--.

line 26, BEFORE "microsampling"

DELETE "the".

line 22, AFTER "wafer;" DELETE "and". Page

line 26, CHANGE "film." TO --film;--. Page

line 21, ADD the following paragraphs

concerning Figures 2A-2C showing a microsampling device.

--FIG. 2A is a top view of microsampling device 20;

o --film; --.
g paragraphs
osampling device.
mpling device 20;
of device 20 of
ample chamber 20C

Pap 3 SN 816,497 FIG. 2B is a sectional side view of device 20 of 2A across lines IIB-IIB, showing sample chamber 20C ar I chamber window 24W; and

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. Krig.

FIG. 2C is a sectional end view of device 20 of
FIG. 2A across lines IIC-IIC.--

Page 7, line 4, AFTER "top surface"

INSERT --11S (sampling side) --.

Page 7, line 4, AFTER "bottom surface"

INSERT --11V (viewing side) --.

Page 7, line 12, CHANGE "FIGS." TO --FIG.s--.

Page 8, line 9, CHANGE "the silicon wafer"

TO --silicon wafer 10d--.

Page 8, line 11, BEFORE "silicon" DELETE --the--.

Page 8, line 11, AFTER "window" INSERT --12d--.

Page 8, line 12, add the following paragraph concerning the microsampling device of Claims 19-26.

--Microsampling device 20 for obtaining a microsample of bodily fluid from a subject, is shown in FIG.s 2A, 2B, and 2C. Silicon substrate 20S has chamber 20C with sampling side 21S and viewing side 21V for containing and viewing the microsample (not shown). Chamber window 24W formed of silicon nitride covers the chamber for closing the viewing side thereof. The silicon substrate may have a thickness of about 500 micrometers, and the silicon nitride window may have a thickness of from about 0.01 of a micrometer to about 5 micrometers. The silicon nitride forming the window is preferably of optical quality. An antireflective coating of a suitable material such as magnesium fluoride may be provided the silicon nitride window. Closure member 24C may be provided over the chamber for closing the sampling side. The closure member engages the substrate around the periphery of the chamber forming an interface therebetween. Needle 26N formed at needle end 26 of the device may be provided for obtaining the sample. Intake bore 26B for transporting the sample into the chamber, extends from the needle end to the chamber along the interface between the closure member and the substrate. Exhaust vent 26V for venting the chamber as the sample is transported into the chamber, extends from the chamber away from the needle end along the interface between the

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